



H-811

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

N. KOFUJI et al

Serial No. 09/363,191

Group Art Unit: 1763

Filed: July 29, 1999

Examiner: L. Alejandro Mulero

For: DRY ETCHING APPARATUS AND A METHOD OF
MANUFACTURING A SEMICONDUCTOR DEVICE

AMENDMENT

Commissioner of Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated May 10, 2002,
please amend the above-identified application as follows. A
Petition and fee for a one-month Extension of Time also
accompany this response.

IN THE CLAIMS

Please cancel claim 7 without prejudice or disclaimer
amend claims 8 and 9 as follows:

8. (Amended) A dry etching apparatus according to claim
1,

wherein said separation plate separates said chamber and
a second area where the pressure is higher than the pressure
in said chamber,

RECEIVED
SEP 19 2002
TC 1700